

First public workshop organized by the Reliability & Characterisation Cluster of PATENT-DfMM

The first public workshop of the Reliability & Characterisation Cluster of PATENT-DfMM network of excellence was held in Sinaia, Romania, 7-8 October, as a joint event with the IEEE International Semiconductor Conference (CAS 2004). The program solely contained contributions given by cluster members: "RF-MEMS reliability research at IMEC" (Ingrid De Wolf, IMEC Leuven), "Reliability research at IXL Bordeaux" (Claude Pellet, IXL Bordeaux), "Accelerated testing: from Microelectronics to MEMS" (Marius Bazu, IMT Bucharest), "Laser accelerated aging of semiconductor chips" (Lucian Galateanu, IMT Bucharest), "BUTE activities in material characterisation" (Andras Poppe, BUTE Budapest), "WP3 database - first results" (Adrian Frumuselu, IMT Bucharest), "Recent work at IEF on materials, testing and packaging of MEMS" (Alain Bosseboeuf, IEF Paris), "Material characterisation at LAAS Toulouse" (Karim Yacine, LAAS Toulouse), "Standardization at micro & nano" (Virgil Ilian, IMT Bucharest), Late news: "About a new STREP in microfluidics" (Catalin Tibeica, IMT Bucharest). Other speakers were: Hoc Khiem Trieu from Fraunhofer IMS Duisburg, Erwan de Gourcuff from Heriot-Watt University, and various participants in CAS 2004. On the second day, the main issues for the next period were discussed during an internal meeting of Reliability & Characterisation Cluster of PATENT-DfMM.

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PATENT-DfMM Workshop planned before DTIP 2005

A public workshop on "Design for Micro & Nano Manufacture" is planned to take place on 30-31 May in conjunction with DTIP. This workshop will be co-organised with the NEXUS MWG Design Modelling Simulation and will feature intermediate results from the Network of Excellence "Design for Micro & Nano Manufacture", and also discuss industry's needs in this area.

DTIP (Symposium on Design, Test, Integration and Packaging of MEMS/MOEMS) will take place at Hotel Eden au Lac, Montreux, Switzerland, 1-3 June 2005 and has recently published a Call for Papers. For more information:

<http://tima.imag.fr/Conferences/dtip>

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softMEMS bought CAD Business Unit from MEMSCAP

softMEMS was created earlier in 2004 by Mary Ann Maher, previously CTO and head of the CAD Business Unit at MEMSCAP, to focus on the CAD tools business. MEMSCAP has sold to softMEMS an exclusive license to sell, market and develop its MEMS design tools, including MEMS Pro and MemMaster. softMEMS also hired most of the previous employees of the MEMSCAP CAD Business Unit, so the transition happened without loss of know-how. softMEMS is maintaining the same product strategy. softMEMS is now a member of the PATENT-DfMM Industry Advisors Board.

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PhD Job Opportunity at HWU

The MicroSystems Engineering Centre is looking for an EU PhD candidate for this newly open position within the Scottish Manufacturing Institute. The candidate must have expertise in software programming (C++ based or Java) and a working knowledge of microsystems technology. The work will deal with haptic based sensing design for the manufacturing and simulation of MEMS. More details can be obtained from the contact.

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Post-doc job opportunity at IMEC

IMEC is looking for a post-doc to work on FEM and reliability of MEMS
Starting date: January 2005.

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DfMM Contact

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The NoE Patent-DfMM aims to establish a collaborative team to provide European industry with support in the field of "design for micro nano manufacture" to ensure that problems affecting the manufacture and reliability of products based on micro nano technologies (MNT) can be addressed before prototype and pre-production.



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